

# Contact Resistance

Semiconductor devices II - EE-567

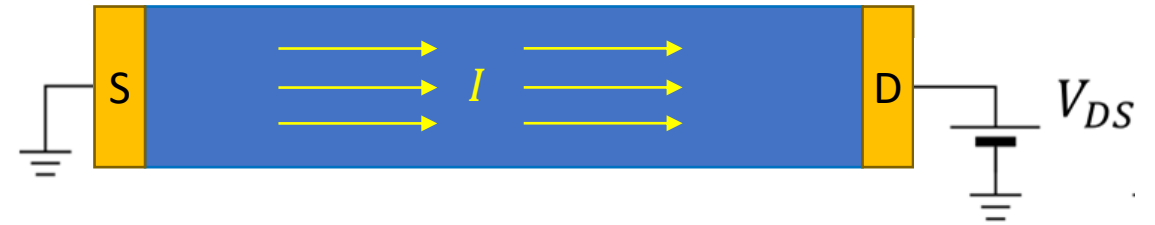
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# Contacts

“Horizontal contacts”:  
contact area = effective contact area



“Vertical contacts”:  
what part of the contact contributes to the conduction?



In general:  $R_{TOT} = R_{sc} + 2R_c + 2R_m$

# Contact resistance

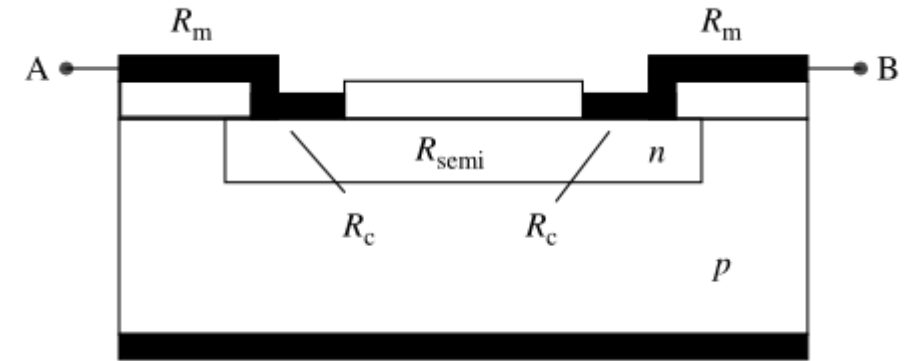
**Semiconductor resistance:**  $\rho \cdot l/A$

**Metal resistance**  $R_m$

**Contact resistance**  $R_c$ : involves some part of the metal, some part of the semiconductor, the structure of the interface

One can think of two quantities of interest in contact resistance measurements:

- Total contact resistance ( $\Omega$ )
- Specific contact resistivity ( $\Omega \text{ cm}^2$ )



# How to measure it?

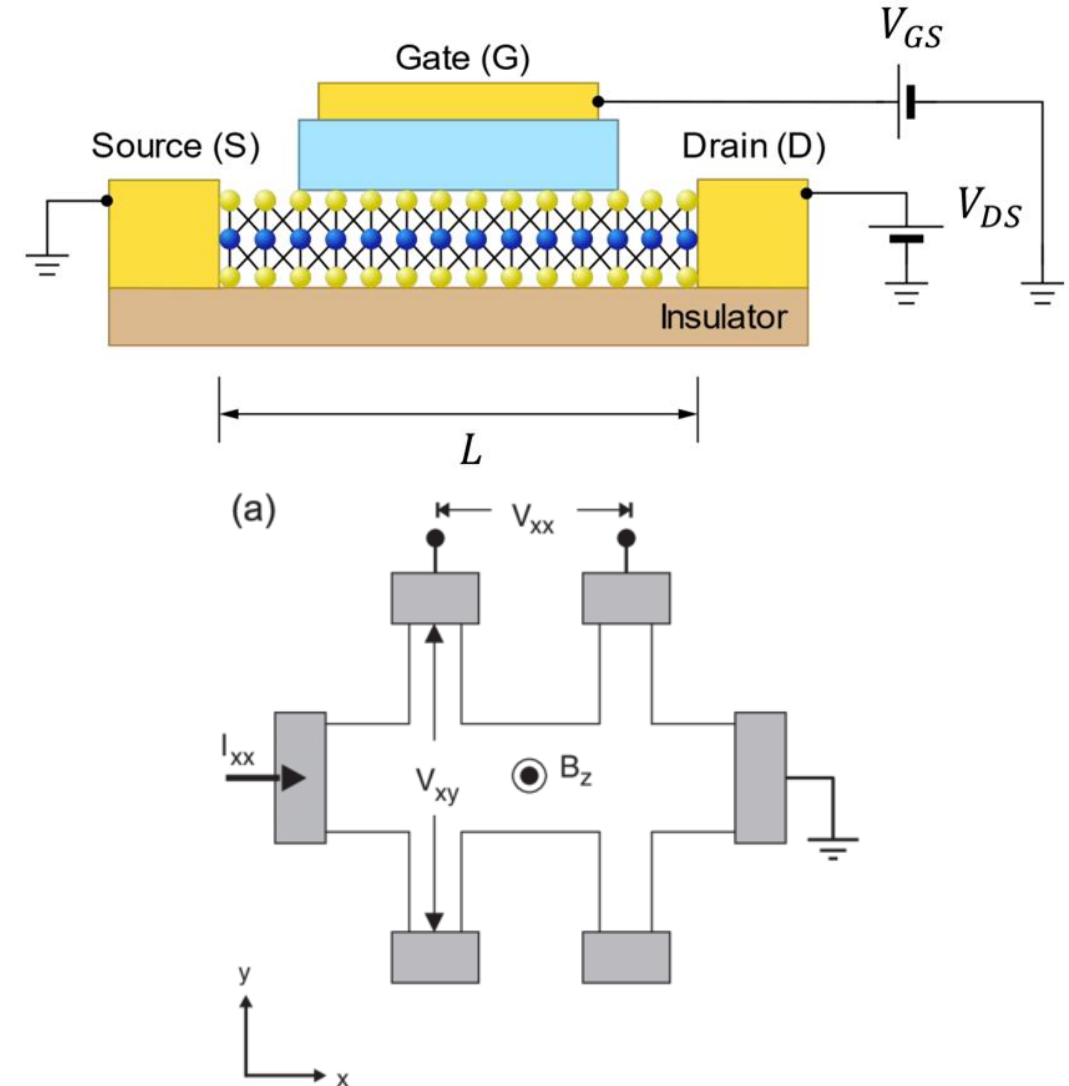
2D Semiconductor

$$R_{2D} = \rho_{2D} \cdot \frac{L}{W}$$

If we can measure  $\rho_{2D}$ , then:

$$R_c = \frac{1}{2} \left( R_{TOT} - \rho_{2D} \frac{L}{W} \right)$$

Example: we make 4-terminal measurements and extract the sheet resistivity from the area between the probes

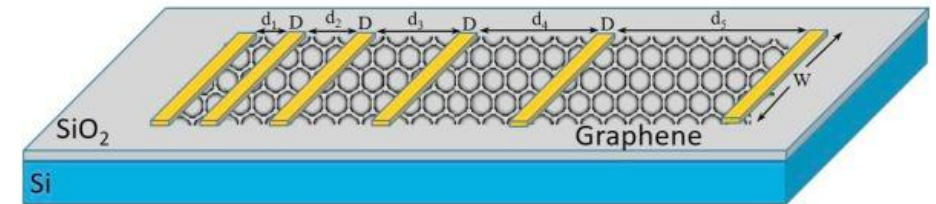


# Another method

$R_{Ti} = \rho_{2D} \frac{d_i}{W} + 2R_c$  is the resistance measured between a pair of contacts  $i, j$

We can extract the contact resistance without any knowledge of  $\rho_{2D}$ :  $R_c = \frac{(R_{Tj}d_i - R_{Ti}d_j)}{2(d_i - d_j)}$

**Assumptions:**



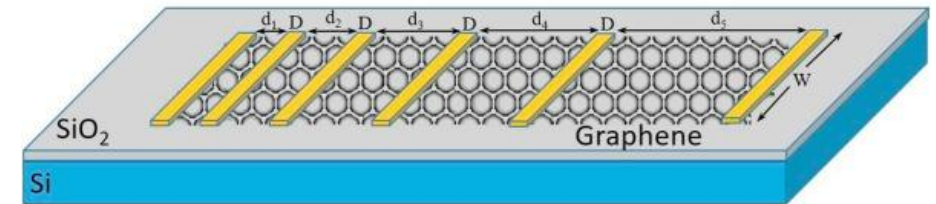
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## Assumptions:

- All contacts are equal
- Material is homogenous



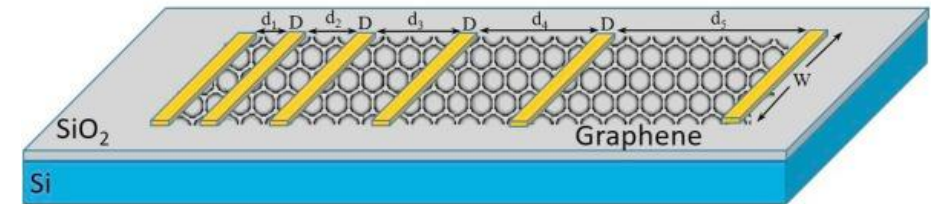
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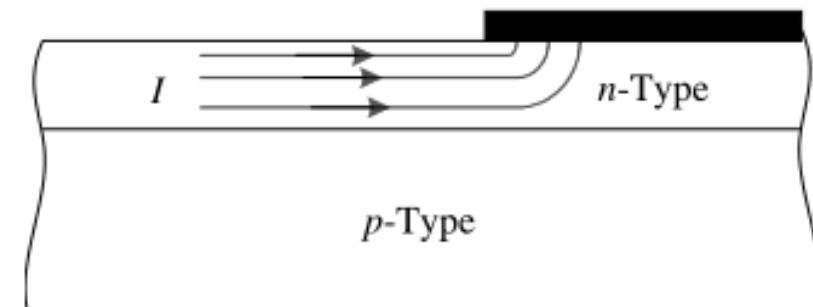
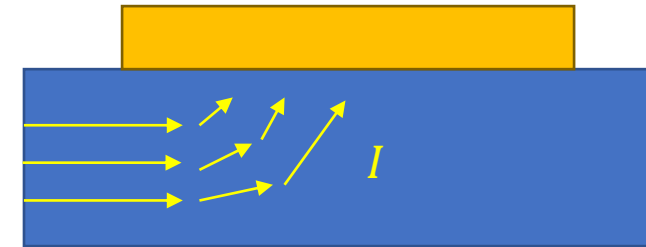


**Problem:** We can measure the total contact resistance ( $\Omega$ ). It would be more interesting to obtain a quantity that does not depend on the shape and size of the contacts!

# Transmission line method

How does the current flow into the contact?

We can describe the contact between metal and the channel as composed of...





# Transmission line method

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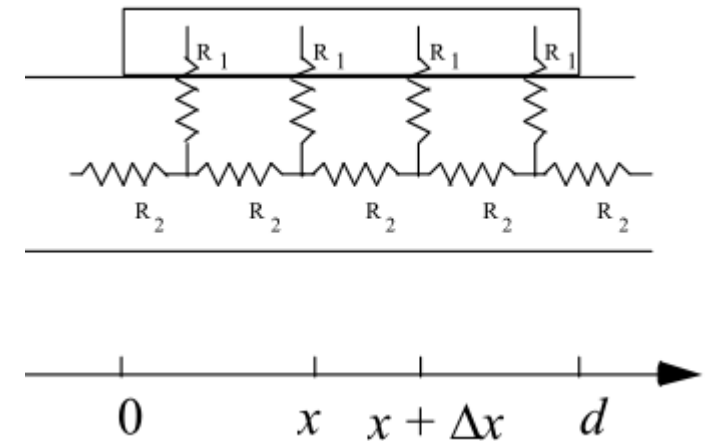
We can describe the contact between metal and the channel as composed of:

Interface resistance for a tiny slice  $\Delta x$ :

$$R_1 = \frac{\rho_c}{W\Delta x}$$

Channel resistance for a tiny slice  $\Delta x$ :

$$R_2 = \rho_s \frac{\Delta x}{W}$$



# Transmission line method

Using Kirchoff's laws:

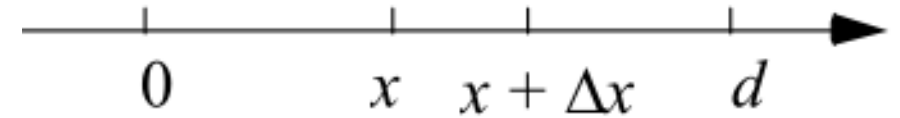
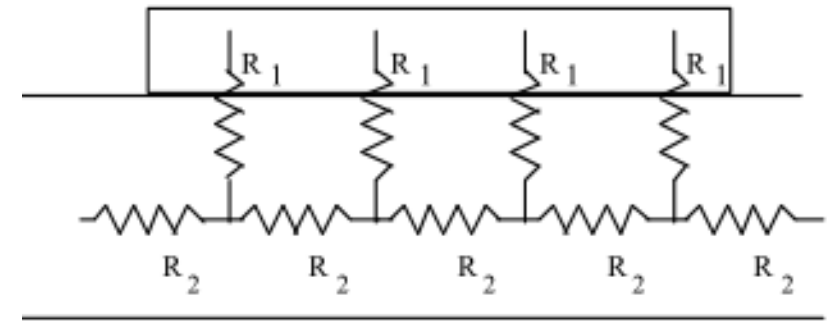
$$V(x + \Delta x) - V(x) = I(x)R_2$$

$$I(x + \Delta x) - I(x) = V(x)/R_1$$

Using the expressions for  $R_1, R_2$ :

$$V(x + \Delta x) - V(x) = I(x) \frac{\rho_s}{W} \Delta x$$

$$I(x + \Delta x) - I(x) = V(x) \frac{W}{\rho_c} \Delta x$$



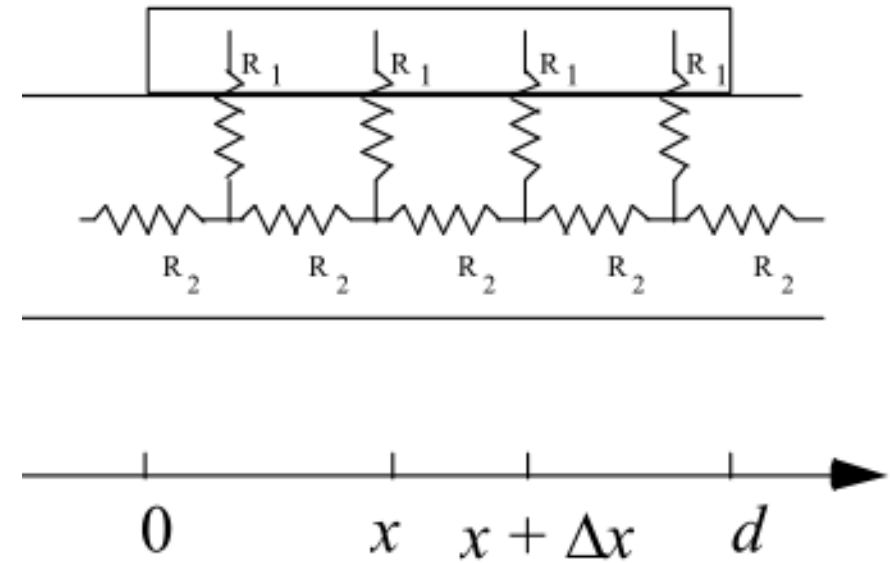
# Transmission line method

So now we have:

$$V(x + \Delta x) - V(x) = I(x) \frac{\rho_s}{W} \Delta x$$

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In the limit  $\Delta x \rightarrow 0$



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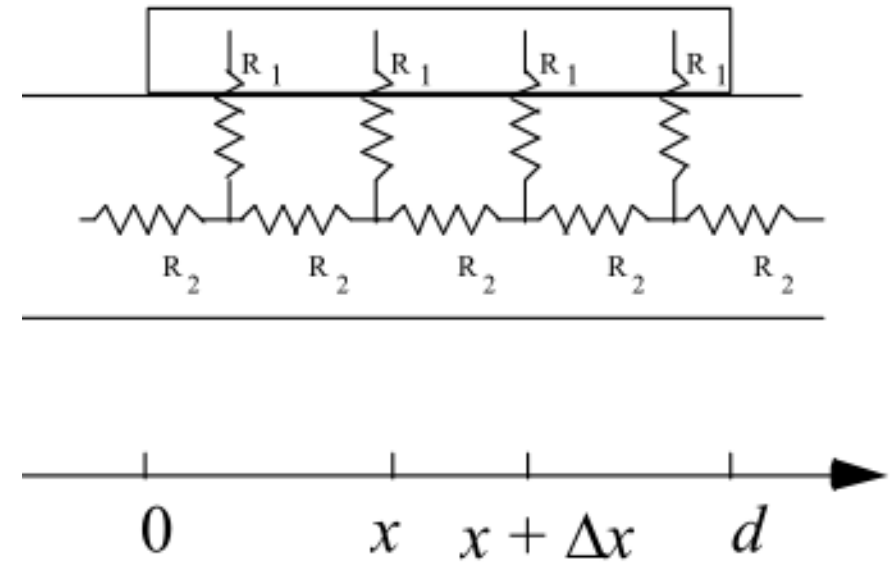
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In the limit  $\Delta x \rightarrow 0$  they become differential equations

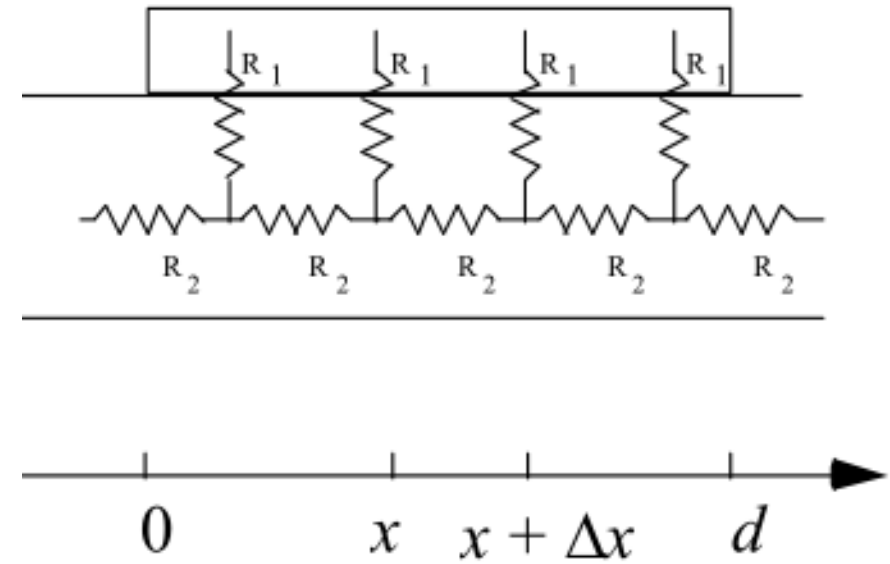
$$\frac{dV}{dx} = I(x) \frac{\rho_s}{W}$$

$$\frac{dI}{dx} = V(x) \frac{W}{\rho_c}$$



# Transmission line method

We can combine everything into one equation:



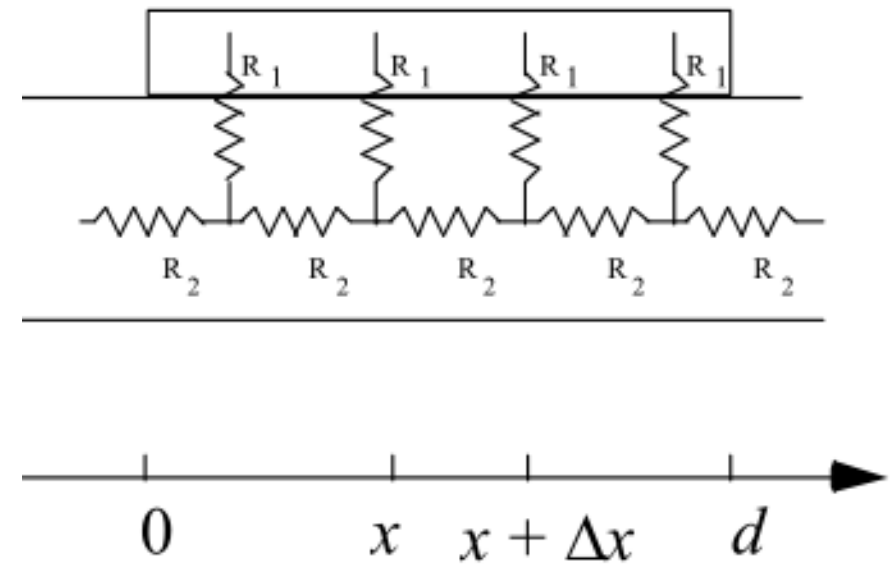
# Transmission line method

We can combine everything into one equation:

- Take the derivative of the second equation:

$$\frac{d}{dx} \left( \frac{d}{dx} I(x) \right) = \frac{d}{dx} \left( V(x) \frac{\rho_s}{W} \right)$$

$$\frac{d^2}{dx^2} I(x) = \frac{dV(x)}{dx} \frac{\rho_s}{W}$$



# Transmission line method

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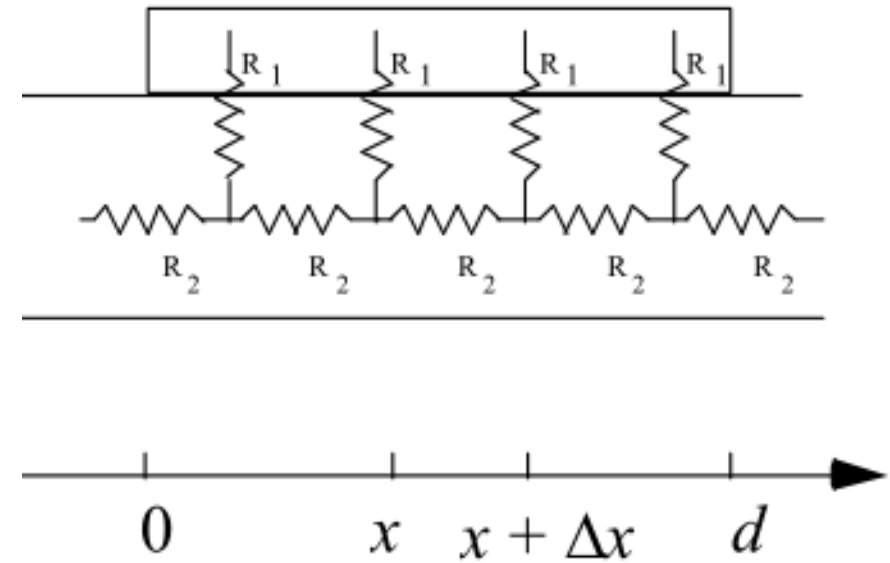
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- Insert the first to substitute  $dI/dx$

$$\frac{d^2 I(x)}{dx^2} = I(x) \frac{\rho_s}{\rho_c}$$



# Transmission line method

We can rewrite this as ( $\lambda = \sqrt{\rho_c/\rho_s}$ ):

$$\frac{d^2 I(x)}{dx^2} = \frac{I(x)}{\lambda^2}$$

General solution:  $I(x) = c_1 e^{x/\lambda} + c_2 e^{-x/\lambda}$

$$I(0) = I_0$$

Which boundary conditions?

$I(d) = 0$  at the end of the contact - no current can flow

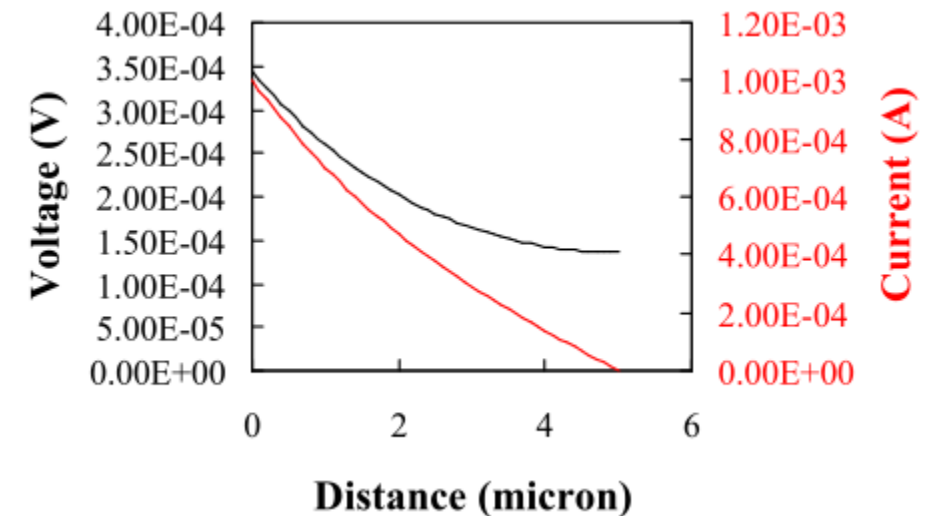
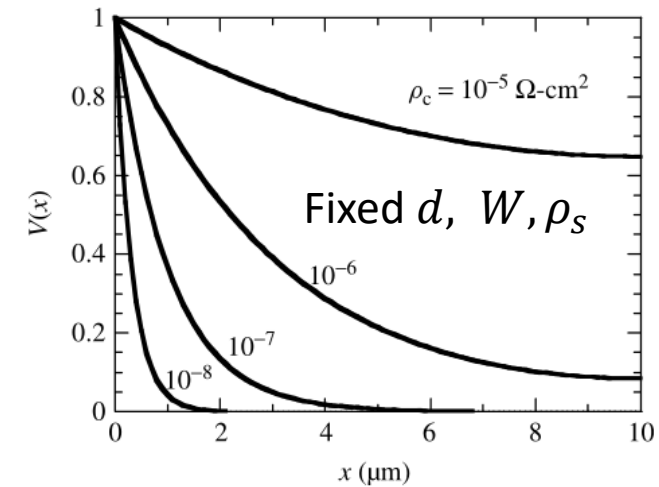


# Transmission line method

After some calculations we find:

$$I(x) = I_0 \frac{\sinh\left(\frac{d-x}{\lambda}\right)}{\sinh\left(\frac{d}{\lambda}\right)}$$

$$V(x) = I_0 \frac{\lambda \rho_s}{W} \frac{\cosh\left(\frac{d-x}{\lambda}\right)}{\sinh\left(\frac{d}{\lambda}\right)}$$



# Transmission line method

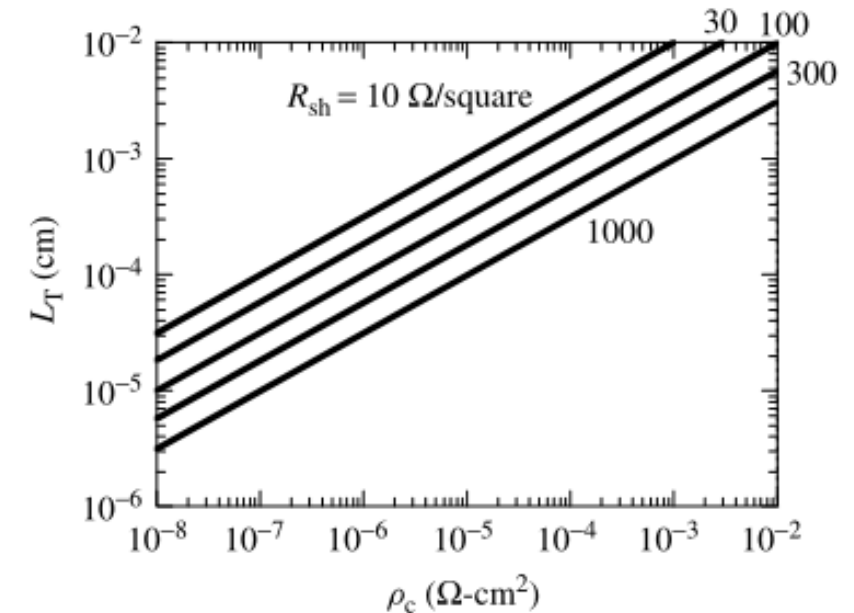
$$I(x) \sim \sinh\left(\frac{d-x}{\lambda}\right)$$

$$V(x) \sim \cosh\left(\frac{d-x}{\lambda}\right)$$

We define “**transfer length**” the quantity

$$\lambda = \sqrt{\rho_c / \rho_s}$$

The transfer length can be thought of as that distance over which most of the current transfers from the semiconductor into the metal or from the metal into the semiconductor.



# Transmission line method

The total contact resistance is

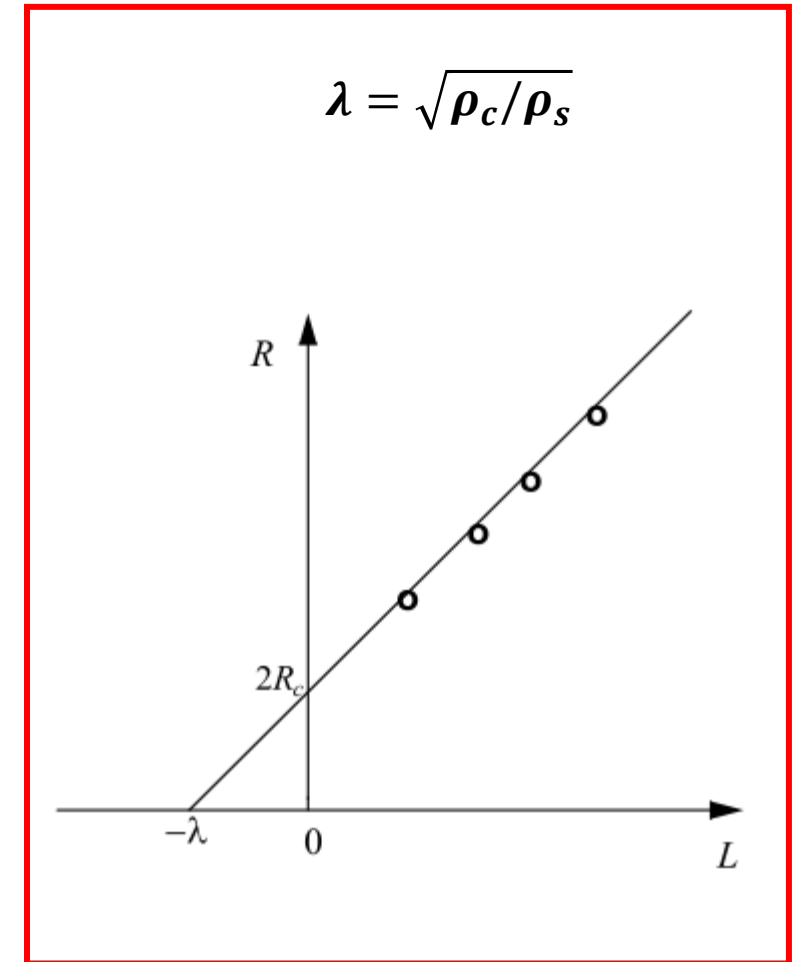
$$R_c = \frac{V(0)}{I(0)} = \frac{\lambda \rho_s}{W} \coth\left(\frac{d}{\lambda}\right)$$

For  $d \gg \lambda$  (contact much longer than the transfer length) we have  $\coth\left(\frac{d}{\lambda}\right) \sim 1$ :

$$R_c \approx \frac{\sqrt{\rho_c \rho_s}}{W}$$

When we measure our device the total resistance will be:

$$R_{TOT} = 2 \cdot \frac{\sqrt{\rho_c \rho_s}}{W} + \rho_s \frac{L}{W}$$



# Transmission line method

The total contact resistance is

$$R_c = \frac{V(0)}{I(0)} = \frac{\lambda \rho_s}{W} \coth\left(\frac{d}{\lambda}\right)$$

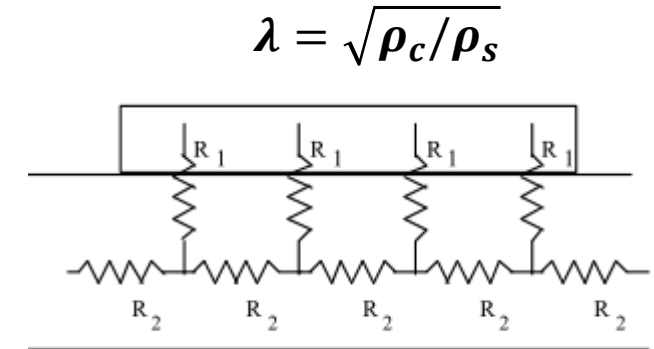
For  $d \ll \lambda$  (contact much shorter than the transfer length) we have

$$\coth\left(\frac{d}{\lambda}\right) \sim \frac{\lambda}{d} + \frac{1}{3}\left(\frac{d}{\lambda}\right) + \dots$$

$$R_c \approx \frac{\rho_c}{Wd} + \frac{1}{3}\rho_s \frac{d}{W}$$

When we measure our device the total resistance will be:

$$R_{TOT} = 2 \cdot \left( \frac{\rho_c}{Wd} + \frac{1}{3}\rho_s \frac{d}{W} \right) + \rho_s \frac{L}{W}$$



$R_c =$

Resistance between metal and channel (parallel connection of all the resistors  $R_1$ )

+

1/3 of the channel underneath the metal (series connection of all resistors  $R_2$ ).